

Description

The PE-Kleen filter combines the latest advances in polyethylene membrane technology with Pall's unique crescent-shaped Ultipleat® filter technology. The result is a cartridge with the outstanding particle retention characteristics required by the semiconductor industry.

The PE-Kleen filter is specifically designed for the filtration of ultra-high-purity chemicals. It is recommended for applications involving antireflective coatings and bulk filtration of 248 nm and 193 nm photoresist. The XP option is available for advanced lithography processes.

Features

- Excellent gel-retention characteristics
- High flow rates
- Low extractables
- 100% integrity tested
- Manufactured in a cleanroom
- Minimized organic extractables by XP option
- XP option guarantees low organic, metal and particle cleanliness for the most advanced processes.



Specifications

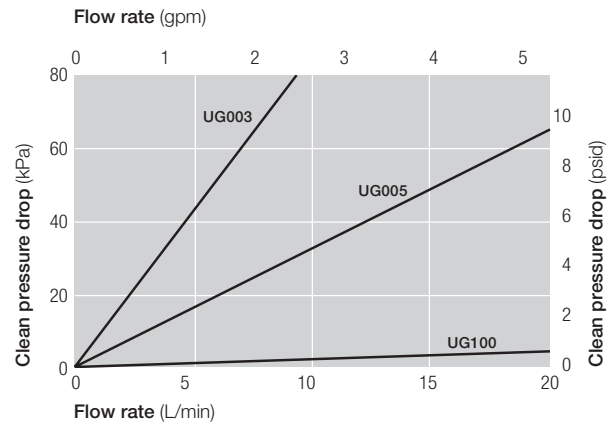
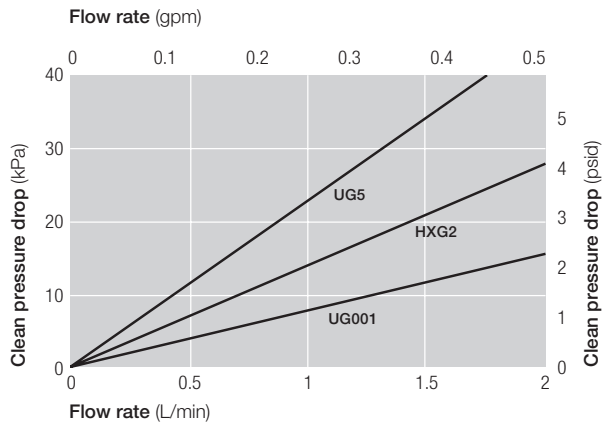
Materials of Construction

Components	Materials
Filter Medium	HDPE ¹
Support and Drainage	HDPE
Core, Cage and End Caps	HDPE
O-ring Options	FEP Encapsulated fluoroelastomer, Perfluoroelastomer

¹ High Density Polyethylene.

Removal Ratings	ABD Filters					
	2 nm	5 nm	10 nm	30 nm	0.05 µm	1.0 µm
Filter Areas	1.3 m ²	1.3 m ²	1.3 m ²	1.1 m ²	1.4 m ²	1.1 m ²
Maximum Operating Temperature	50 °C / 122 °F					
Maximum Forward Differential Pressure	340 kPa @ 40 °C / 49 psid @ 104 °F					

Typical Flow Characteristics - 1 cP fluid, 20 °C



Part Numbers / Ordering Information^{2,3}

ABD 1 UG 2 3 E 4

Table 1

Code	Nominal length (mm / in)
1	254 / 10
2	508 / 20
3	762 / 30

Table 2

Code	Removal Ratings
2	2 nm
5	5 nm
001	10 nm
003	30 nm
005	0.05 µm
100	1.0 µm

Table 3

Code	Configurations
3	222 O-ring open end flat closed end
7	226 O-ring open end fin on closed end
8	222 O-ring open end fin on closed end

Table 4

Code	O-ring Materials
J	EPR
H1	FEP Encapsulated fluoroelastomer
H11	Perfluoroelastomer

² Filter elements may not be available in all configurations. Contact your local Pall representative for availability.

³ For XP option, add -XP to end of part number for 2 - 10nm removal ratings and 10 - 20 inches.



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The information provided in this literature was reviewed for accuracy at the time of publication. Product data may be subject to change without notice. For current information consult your local Pall distributor or contact Pall directly.

IF APPLICABLE Please contact Pall Corporation to verify that the product conforms to your national legislation and/or regional regulatory requirements for water and food contact use.

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